

A method for producing a fused silica glass containing titania, comprising:
synthesizing particles of silica and titania by delivering a mixture of a silica precursor and a titania precursor to a burner;

consolidating the porous preform into a dense glass.

3. The method of claim 1, wherein the silica and titania particles are deposited at
15 a temperature below that required to consolidate the porous preform into dense glass.

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5. The method of claim 1, further comprising dehydrating the porous preform by exposing the porous preform to a heated, halide-containing atmosphere prior to consolidation.

7. The method of claim 5, wherein the heated, halide-containing atmosphere comprises fluorine.

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8. The method of claim 5, wherein the temperature of the heated, halide-

containing atmosphere is in a range from 900 to 1100°C.

9. The method of claim 1, wherein the glass contains 2 to 12% by weight titania.
- 5 10. A method for producing a fused silica glass containing titania and having low OH content, comprising:
 - synthesizing particles of silica and titania by delivering a mixture of a silica precursor and a titania precursor to a burner;
 - growing a porous preform by successively depositing the particles on a
 - 10 deposition surface while rotating and translating the deposition surface relative to the burner;
 - dehydrating the porous preform by exposing the porous preform to a heated, halide-containing atmosphere; and
 - consolidating the dehydrated porous preform into a dense glass.
- 15 11. The method of claim 10, wherein the heated, halide-containing atmosphere comprises chlorine.
12. The method of claim 10, wherein the heated, halide-containing atmosphere
- 20 comprises fluorine.
13. The method of claim 10, wherein a translation speed of the deposition surface is adjusted to maintain a substantially constant distance between the porous preform and the burner during deposition.
- 25 14. The method of claim 10, wherein the silica and titania particles are deposited at a temperature below that required to consolidate the porous preform into dense glass.
- 30 15. The method of claim 14, wherein consolidating the porous preform into dense glass comprises heating the porous preform to a temperature in a range from 1200 to 1900°C.

16. A mask blank for extreme ultraviolet lithography made by a process comprising:
- synthesizing particles of silica and titania by delivering a mixture of a silica precursor and a titania precursor to a burner;
 - growing a porous preform by successively depositing the particles on a deposition surface while rotating and translating the deposition surface relative to the burner;
 - consolidating the porous preform into a dense glass; and
 - finishing the dense glass into a mask blank.
17. The mask blank of claim 16, comprising the glass contains 2 to 12% by weight titania.
18. A mask blank for extreme ultraviolet lithography made by a process comprising:
- synthesizing particles of silica and titania by delivering a mixture of a silica precursor and a titania precursor to a burner;
 - growing a porous preform by successively depositing the particles on a deposition surface while rotating and translating the deposition surface relative to the burner;
 - dehydrating the porous preform by exposing the porous preform to a heated, halide-containing atmosphere;
 - consolidating the porous preform into a dense glass; and
 - finishing the dense glass into a mask blank.
19. The mask blank of claim 18, wherein the glass contains 2 to 12% titania.